

	Hits	Search Text	DBs
23	70	((heat\$4 or anneal\$7 or bak\$4 or cur\$4) same (pattern or mask) same (trench\$4 or hole) same ((liquid or solution) near26 (metal\$4 or pattern or hydrophobic\$4 or polymer\$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer\$3 or photosenstive or radiation\$6sensitive)) and ((trench\$3 or hole or contact\$6hole or via or (aspect\$8 near6 ratio)) same (fill\$4 or (conformal\$4 near9 (fill\$4 or deposit\$4 or layer\$4))) same (plural\$4 or multiple\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	37	S26 and (develop\$4 or strip\$4 or remov\$4) and ((remov\$4 or eliminat\$4 or strip\$4) same (liquid or deposit\$4 or solution or hydrophobic or polymer\$4 or metal\$3) same ((pattern or mask) near16 (portion or region or area)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	75	((heat\$4 or anneal\$7 or bak\$4 or cur\$4) same (pattern or mask) same (trench\$4 or hole) same ((liquid or solution) near26 (metal\$4 or pattern or hydrophobic\$4 or polymer\$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer\$3 or photosenstive or radiation\$6sensitive)) and ((trench\$3 or hole or contact\$6hole or via or (aspect\$8 near6 ratio)) same (fill\$4 or immers\$4 or (conformal\$4 near9 (fill\$4 or deposit\$4 or layer\$4))) same (plural\$4 or multiple\$4))	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	37	S28 Not S27	US-PPGPUB; USPAT
27	38	S28 NOT S27	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	206	<p>((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (pattern or mask) same (trench\$4 or hole or opening or via) same ((liquid or solution or immers\$4) near26 (metal\$4 or pattern or hydrophobic\$4 or polymer\$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer\$3 or photosensitive or radiation\$6sensitive)) and ((trench\$3 or hole or contact\$6hole or via or (aspect\$8 near6 ratio) or opening) same (fill\$4 or dip\$4 or immers\$4 or (conformal\$4 near9 (fill\$4 or deposit\$4 or layer\$4))) same (plural\$4 or multiple\$4 or several))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	131	S31 NOT S28	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB